



U.S. PATENT & TRADEMARK OFFICE
N. 10/050,322

1756
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Tsai et al.

Group Art Unit: 1756

Serial No.: 10/050,322

Examiner: N. M. Barreca

Filed: 01/15/2002

In Response to Office Action

Dated: 06/23/2003

For: A BI-LAYER PHOTORESIST DRY DEVELOPMENT AND
REACTIVE ION ETCH METHOD

RECEIVED

SEP 29 2003

TC 1700

Attorney Docket No.: 67,200-613

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I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, Va 22313-1450

Date:

Sept. 23/03


Kathy Dixon

RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, Va 22313-1450

Dear Sir:

In response to an Office Action mailed 06/23
/2003, please enter the following amendments and consider the
following remarks.

10/06/2003 CSIAS1 00000004 500484 10050322
01 FC:1202 54.00 DA